

Modeling Thin Film, Buckle-Driven Delamination along a Metal/Polymer Interface in a Stressed Overlayer Test

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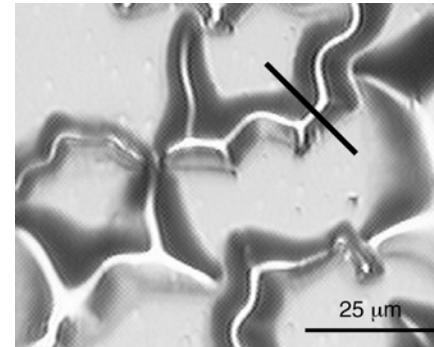
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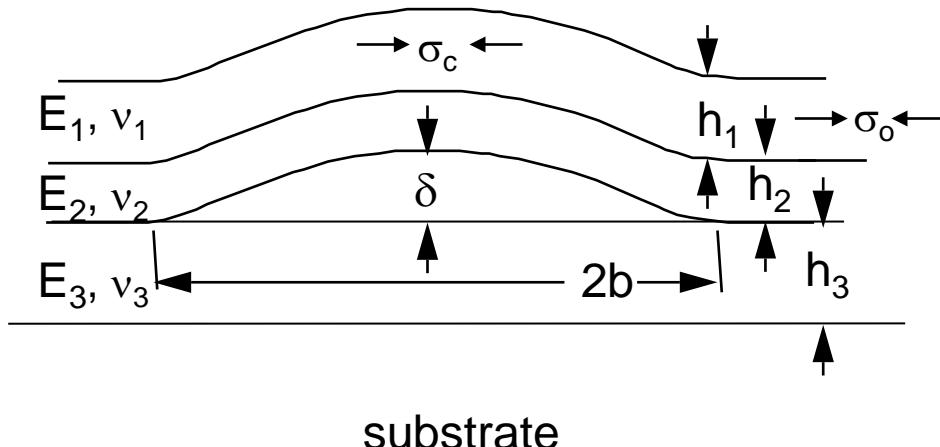
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Modeling Stressed Overlayer Test

- The reliability of components with thin film polymer/metal interfaces is often controlled by the toughness of the interface.
- One method of measuring the toughness of such interfaces is the stressed-overlayer test:
 - metal substrate coated with thin polymer film to create interface of interest.
 - deposit overlayer with very high residual compressive stress on top of polymer.
 - height of induced blisters used to infer toughness using mechanics models.



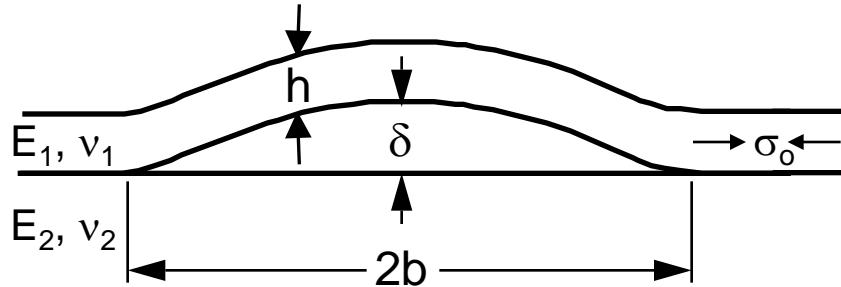
Tungsten/Epoxy/Aluminum deposited on a thick glass substrate



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Buckle-driven thin film delamination: one-dimensional, straight-sided blister

- Analytic results for a thin elastic film on a rigid substrate are well established (Chai et.al, 1981; Evans and Hutchinson, 1984; Gille, 1985; Whitcomb, 1986).
- There are some published results for the case of a compliant substrate (Cotterell and Chen, 2000; Yu and Hutchinson, 2002), however, results for a very stiff film on a very compliant substrate have not been fully determined (e.g., W/PMMA).
- There appears to be little work aimed at including the effects of substrate yielding and crack flank friction in FEA simulations.



- Requires a pre-existing delamination.
- Nonlinear, large deflection analysis.
- No crack growth until σ_o exceeds the critical buckling stress.
- Based upon dimensional considerations

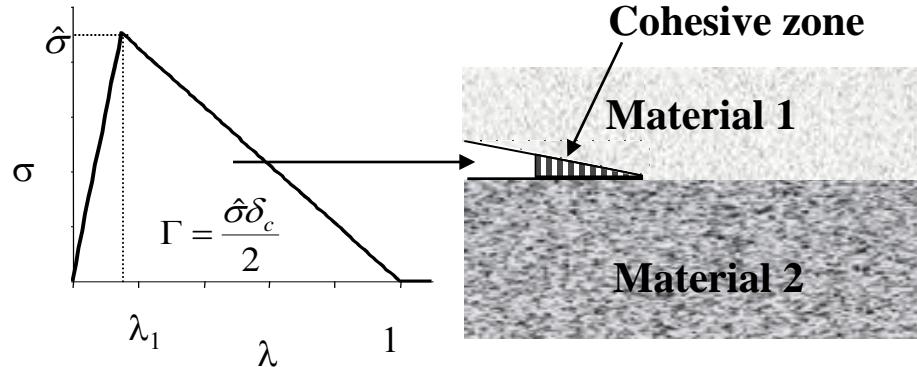
$$\frac{b}{h} = f\left(\frac{\Gamma}{G_o}, \frac{\sigma_o}{E_1}, \alpha, \beta\right) \quad \text{where} \quad G_o = \sigma_o^2 h / (2E_1)$$



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Cohesive Zone Model

- Material separation based on a specified traction-separation($\sigma - \delta$) relationship.
- Well-suited for modeling interfacial crack growth when crack path is well defined.
- Crack growth is a natural outcome of the solution, bond failure is a gradual process with tractions resisting separation.
- Key parameters are the interfacial strength $\hat{\sigma}$ and the work of separation/unit area Γ (i.e., the intrinsic interfacial toughness).
- Mesh-independent results.



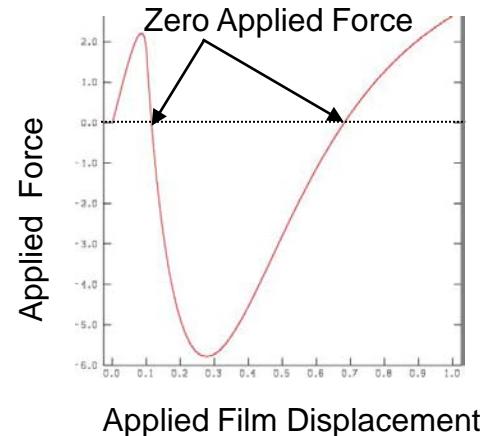
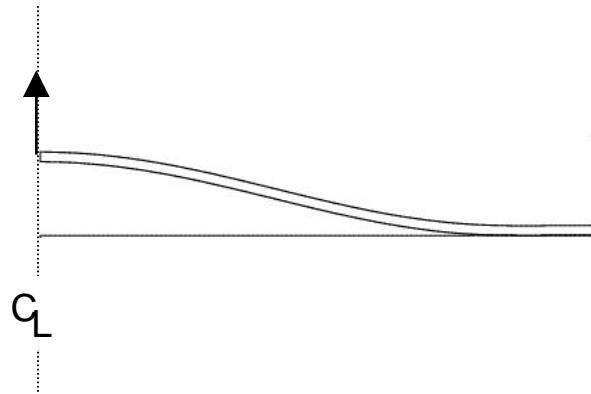
- Usually defined in terms of a potential that depends on a scalar effective separation.
- Similar to model introduced by Tvergaard and Hutchinson (J. Mech. Phys. Solids, **41**, 1119, 1993).



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Technique for analyzing a buckle-driven delamination

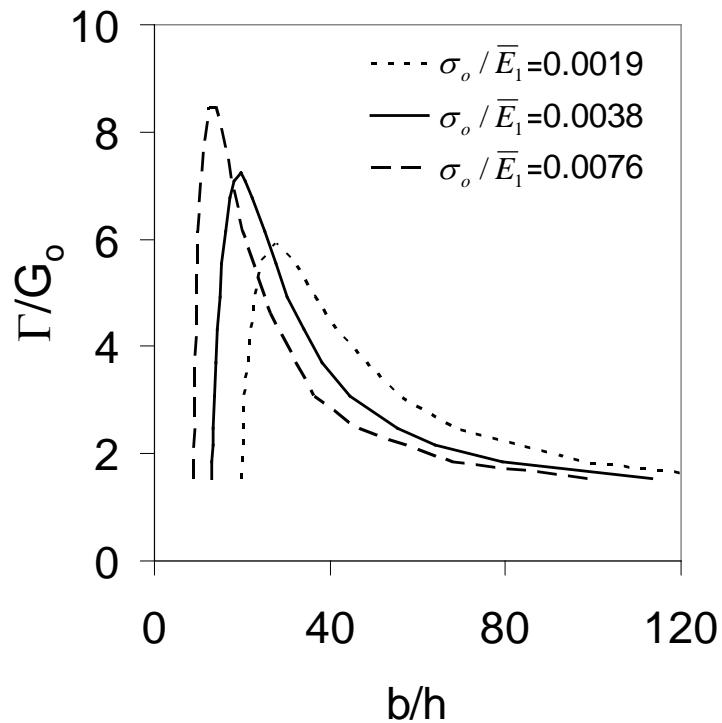
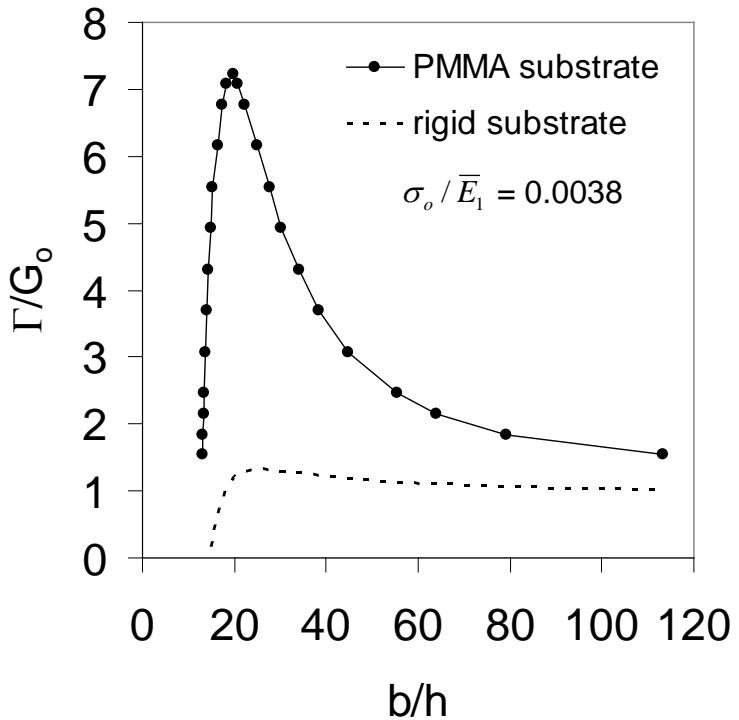
For a prescribed σ_o , apply monotonically increasing film displacement and monitor associated force.



- For a prescribed σ_o , perform CZ finite element simulation to determine delamination width (b) and height (δ) for interface with toughness Γ .
 - displace center of buckle upwards (i.e., an external agent prescribes the buckle height δ).
 - monitor the associated applied force
 - when the applied force does equal zero, a free-standing, buckled exists.
- Perform calculations for broad range of Γ to determined relationship between delamination height (width) and interfacial toughness for fixed σ_o .
- FE model contains a small pre-existing flaw shorter than the critical buckling length.



Results for a 0.1 μm W film on a thick PMMA substrate with $\sigma_o=1.7 \text{ GPa}$ demonstrated effect of substrate compliance.

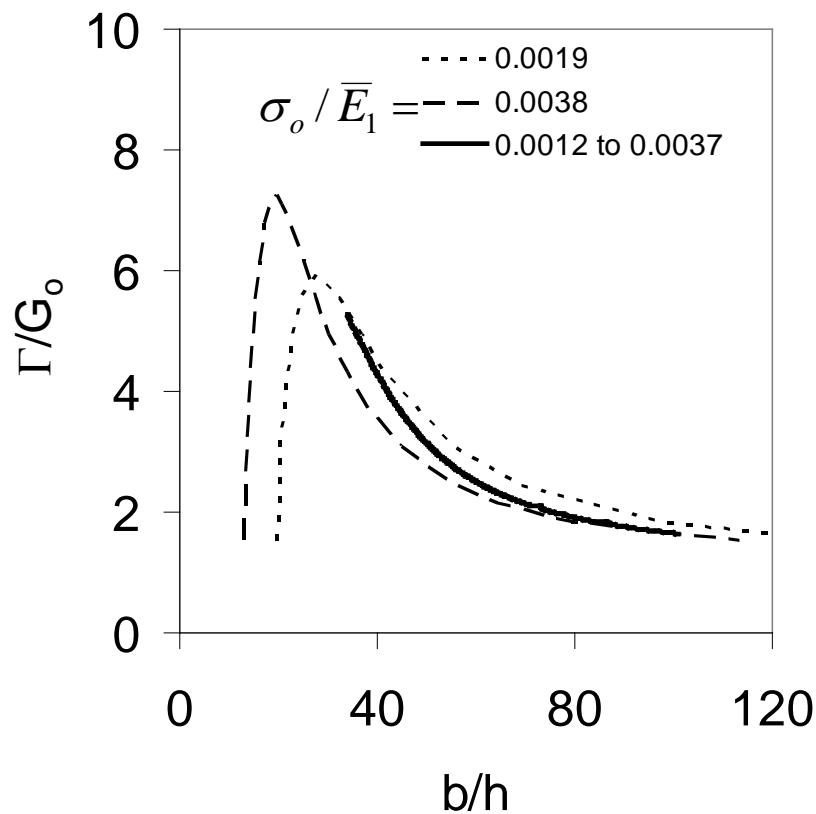


- Note scaling $\frac{b}{h} = f\left(\frac{\Gamma}{G_0}, \frac{\sigma_o}{\bar{E}_1}, \alpha, \beta\right)$
where $G_o = \sigma_o^2 h / (2\bar{E}_1)$ is the long crack energy release rate. $G_o = 0.325 \text{ J/m}^2$
- These results are for W/PmmA with $\alpha = 0.985$, $\beta = 0.227$
- CZ length in these calculations was $\sim 3\text{-}5h$



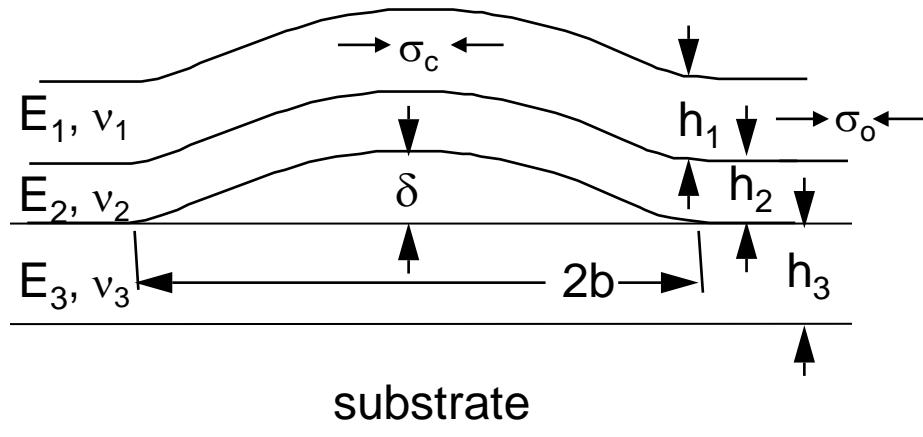
Another calculation approach

- Initially apply load to lift up preexisting delaminated region (create an initial “imperfection”).
- Then monotonically increase the film compressive stress while decreasing applied load (fully release applied load prior to any delamination growth).
 - note σ_o / \bar{E}_1 increases with increasing σ_o .
- Results consistent with previous approach.
- Calculation for W/PMMA with $h = 0.1 \mu\text{m}$, with $\Gamma = 0.5 \text{ J/m}^2$ and for an initial delamination = $3 \mu\text{m}$.



W-overlayer on an epoxy film on an aluminized glass substrate

- To provide focus, analyzed a previously reported, stressed overlayer test configuration (SAND2002-8567).
 - Substrate: 0.2 μm Al sputtered on a glass microscope slide.
 - Film: 0.024, 0.164 or 0.615 μm thick Epon 828/T403 epoxy layer spin-coated on the substrate (film is material 2).
 - Stressed overlayer: 0.22 μm W with a $\sigma_o=2.2$ GPa residual biaxial compressive film stress sputtered on top of the epoxy film (overlayer is material 1).
 - Failure at the epoxy/Al interface.



Tungsten (W): $E_1=410$ GPa $\nu_1=0.28$
Epoxy: $E_2=3.5$ GPa $\nu_2=0.35$
Aluminum (Al): $E_3=70$ GPa $\nu_3=0.33$
Substrate: thick and rigid

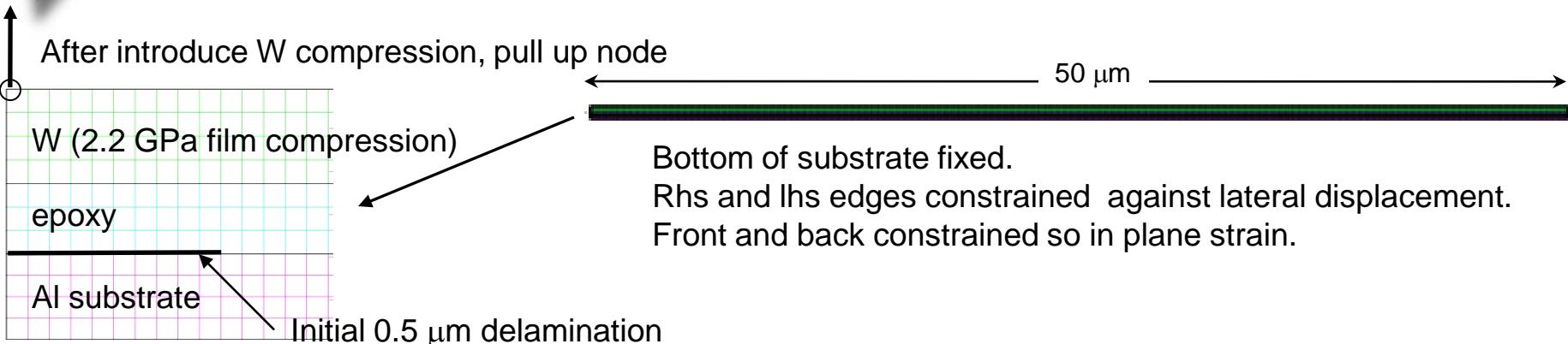
Measured half-buckle width b

h_2 (μm)	b (μm)
0.024	4.4
0.164	6.5
0.615	6.0



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Test calculations for W/0.164 μm epoxy/Al specimen

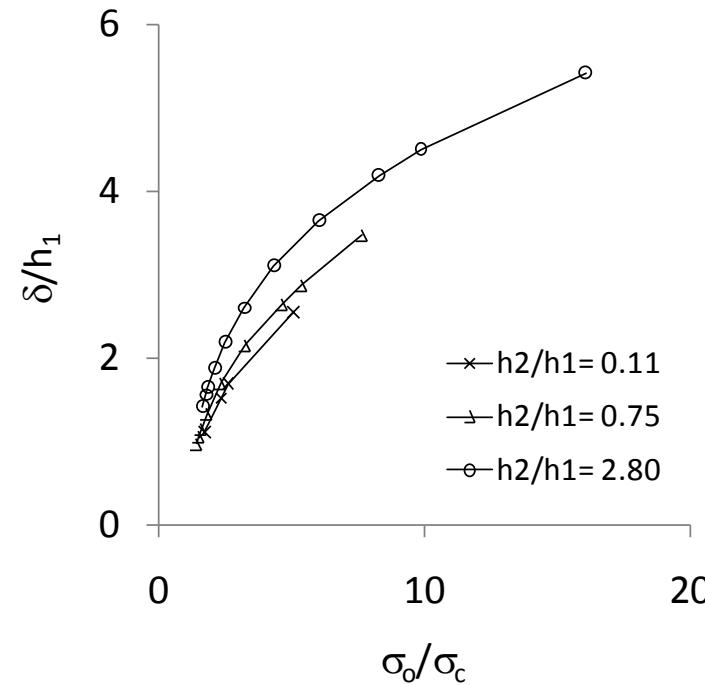
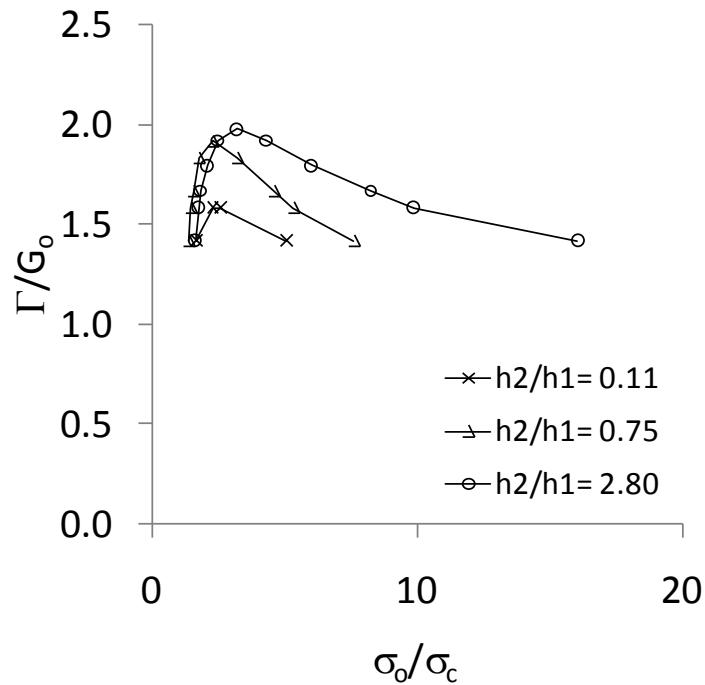


- Examined how choice of interface strength $\hat{\sigma}$ affects solution.
 - A higher $\hat{\sigma}$ is associated with a lower δ_c .
 - Length of the cohesive zone scales with δ_c .
 - Results for a W/0.164 μm epoxy/Al lay-up with $\Gamma = 1.7 \text{ J/m}^2$
 - b measured from tip of cohesive zone
 - chose $\hat{\sigma}$ so that CZ length/ $h_1 \sim 1-2$

	$\hat{\sigma} = 120 \text{ MPa}$	$\hat{\sigma} = 170 \text{ MPa}$	$\hat{\sigma} = 240 \text{ MPa}$
δ/h_1	3.5	3.5	3.4
b/h_1	36.4	34.5	33.9
CZ length/ h_1	4	2	1

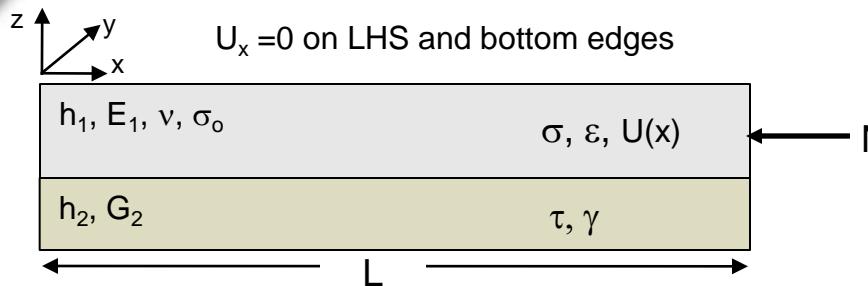


Results: effect of epoxy thickness



- Calculated Γ/G_0 and δ/h_1 depend on W overlayer-to-epoxy film thickness ratio h_2/h_1 .
- Maximum $\Gamma/G_0 > 1.33$ exceeds the rigid substrate ratio; as is the case for a thick compliant substrate.
- FEA shows that there is horizontal deflection of the overlayer at the buckle front towards the center of the buckle (will call this overlayer edge-displacement).

Shear-lag analysis estimate of overlayer edge-displacement during buckling



$$\frac{d\sigma}{dx} = \frac{\tau}{h_1} \quad (\text{eq. 1, equilibrium})$$

$$\varepsilon = \frac{d}{dx} U(x) = (\sigma_o + \sigma) / \bar{E}_1 \quad \text{where } \bar{E}_1 = E_1 / (1 - \nu^2) \quad (\text{eq. 2, W overlayer})$$

$$\gamma = \frac{U(x)}{h_2} = \tau / G_2 \quad (\text{eq. 3, epoxy})$$

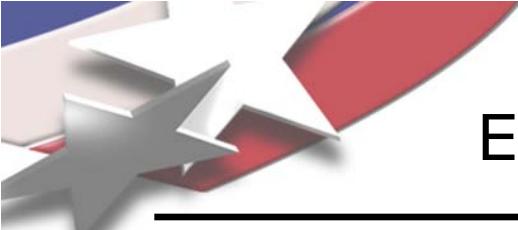
$$\frac{d^2 U(x)}{dx^2} - k^2 U(x) = 0 \quad \text{where } k^2 = G_2 / (h_1 h_2 \bar{E}_1) \quad (\text{eq. 4, governing ODE; combine eqs. 1-3})$$

$$U(0) = 0 \text{ and } \frac{dU(L)}{dx} = \frac{\sigma_o}{\bar{E}_1} - \frac{N_c}{h_1 \bar{E}_1} \quad (\text{eq. 5, BCs for governing ODE})$$

$$U^* = U(L) = (\sigma_o - N_c / h_1) / (k \bar{E}_1) \quad (\text{eq. 6, solution for edge-displacement, } U^*, \text{ in limit of long strip; i.e., } kL \gg 1)$$

- The shear-lag analysis assumes
 - W-overlayer carries only axial loads
 - epoxy layer carries only shear loads
- Note:
 - $\varepsilon_y = 0$ (plane strain) and $\sigma_z = 0$ (beam-like)
 - σ_o is the residual overlayer stress (positive in compression)
 - N_c = critical classical buckling load
 - Analyzing unbuckled portion of strip (i.e., buckle would be beyond rhs of model)





Extended rigid substrate analytic solution

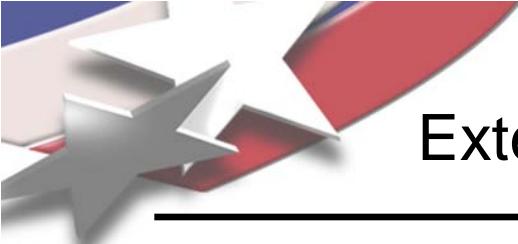
- Extension for a stiff overlayer (e.g., W) on a very compliant film (e.g., epoxy) that fails at the film/substrate interface where the substrate is also relatively stiff (e.g., Al).
- Modify rigid substrate analytic solution (see Mixed Mode Cracking in Layered Materials, Hutchinson and Suo, Advances in Applied Mechanics, 1992) by:
 - 1) Using the effective, plane strain EI per unit width for the combined overlayer/film bimaterial beam (see Formulas for Stress and Strain, by Roark and Young for equations to calculate $D_e = (EI)_e$ per unit width).
 - 2) Appending a term associated with overlayer edge-displacement to the “change in the resultant from the unbuckled state”, ΔN , that is used in the formula defining the amplitude of the buckling deflection.

$$\left(\frac{\delta}{h_1}\right)^2 = \frac{4(\Delta N + N^*)}{3N_c} \quad \text{where } \Delta N = N_o - N_c \text{ with } N_o = \sigma_o h_1, \quad N_c = \frac{\pi^2 D_e}{b^2}, \quad \text{and} \quad N^* = \bar{E}_1 h_1 U^* / b \quad (\text{eq. 7})$$

(recall that U^* is the overlayer edge-displacement and b is the buckle half-width)



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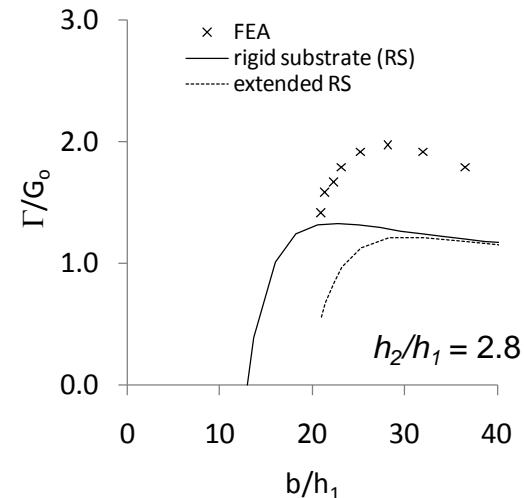
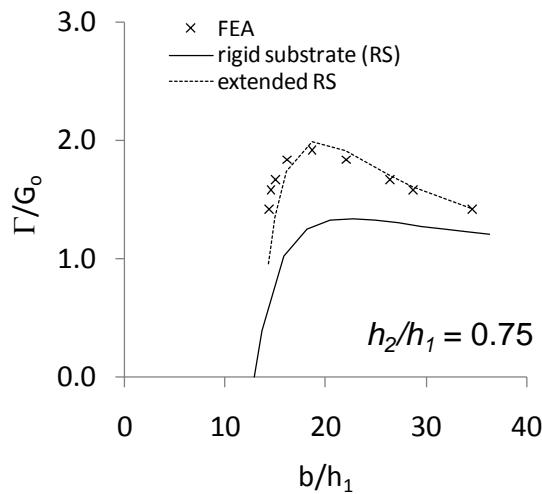
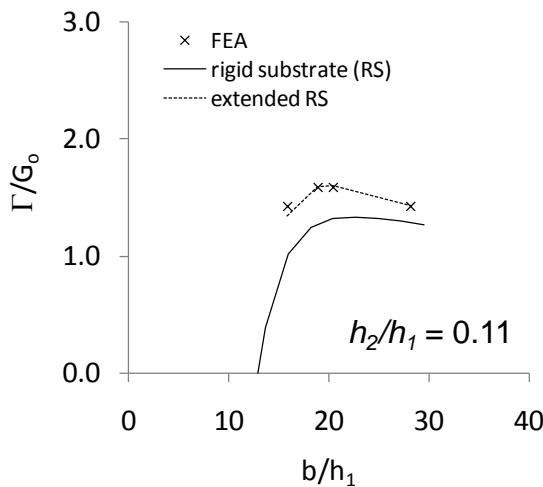
Extended rigid substrate (ERS) analytic solution

Order of calculations for ERS solution; assume know half-buckle width b , layer thicknesses and elastic properties.

1. Calculate D_e (see Roark and Young)
2. Calculate N_c eq. 7
3. Calculate U^* eq. 6
4. Calculate δ eq. 7
5. Calculate $G = \frac{(N_c \delta)^2}{8D_e} + \frac{(\Delta N)^2}{2\bar{E}h_l}$
6. Calculate G/G_o where $G_o = N_o^2 / (2\bar{E}h_l)$



Compare enhanced rigid substrate analytic solution and FEA results

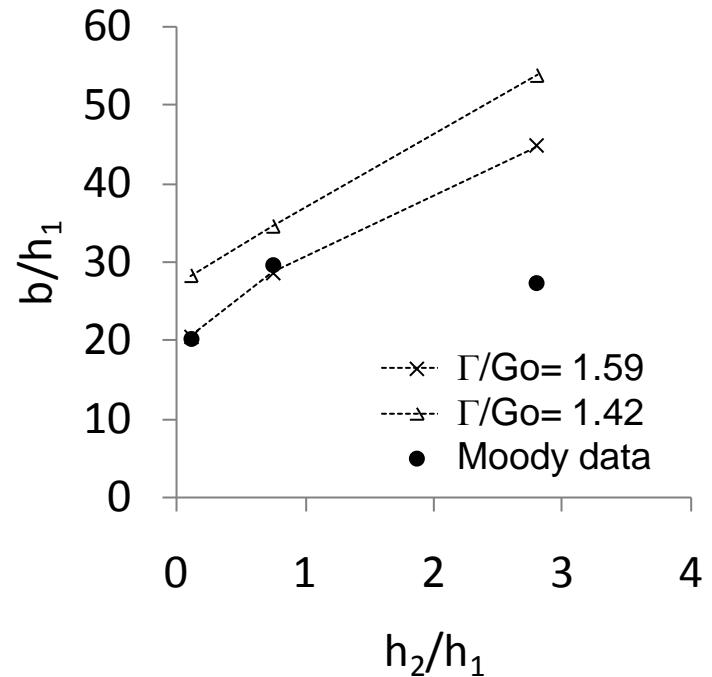


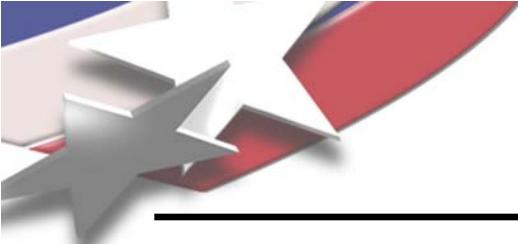
- Enhance Rigid Substrate (ERS) analytic result, which incorporates a shear-lag estimate for horizontal edge-displacement during buckling, is in good agreement with FEA results for the particular specimen analyzed here when $h_2/h_1 = 0.11$ and 0.75 .
- As might be anticipated, the ERS solution was in poor agreement with the FEA results when $h_2/h_1 = 2.8$ (when use of shear-lag analysis is questionable).
- Overlayer edge-displacement provided largest correction to rigid substrate analysis (D_e had small effect).



FEA used to reduce experimental data

- For an \sim constant mode-mixity ψ (or if independent of ψ), FEA results for a constant Γ should predict the variation in b/h_1 with h_2/h_1 .
- Finite element results suggest that $\Gamma/G_o=1.6$ is a good fit to data for $h_2/h_1 = 0.11$ and 0.75.
 - Corresponds to $\Gamma=1.9 \text{ J/m}^2$, a relatively high value, suggesting epoxy yielding is contributing to the apparent toughness.
- Data point for $h_2/h_1 = 2.8$ lies well below the $\Gamma/G_o=1.6$ prediction.
 - Finite element results suggest contact behind the cohesive zone --- crack flank friction is not accounted for in the analysis and could generate an enhanced mode-mixity effect.

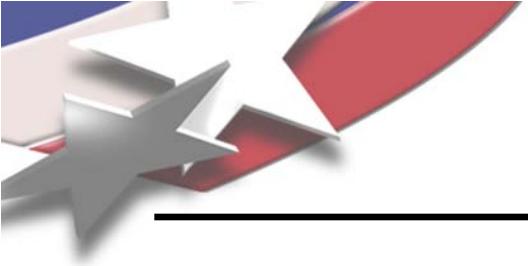




Summary

- Performed cohesive zone finite element analysis of a W/epoxy/Al stressed overlayer specimen that has been used previously at SNL.
 - Showed that variations in the epoxy layer thickness can have a significant effect.
 - Showed that the overlayer “edge-displacement” (enabled by relatively low epoxy compliance) is the primary cause of differences from the rigid substrate idealization.
 - Showed how applicability of rigid substrate analytic solution can be enhanced to include overlayer edge-displacement through a simple, shear-lag based correction (preliminary result, have not determined range of applicability, etc.).
 - Comparison with experimental data indicates that plasticity and crack flank friction affects measured toughness --- topics that must be addressed in future work so can model mode-mixity effects.



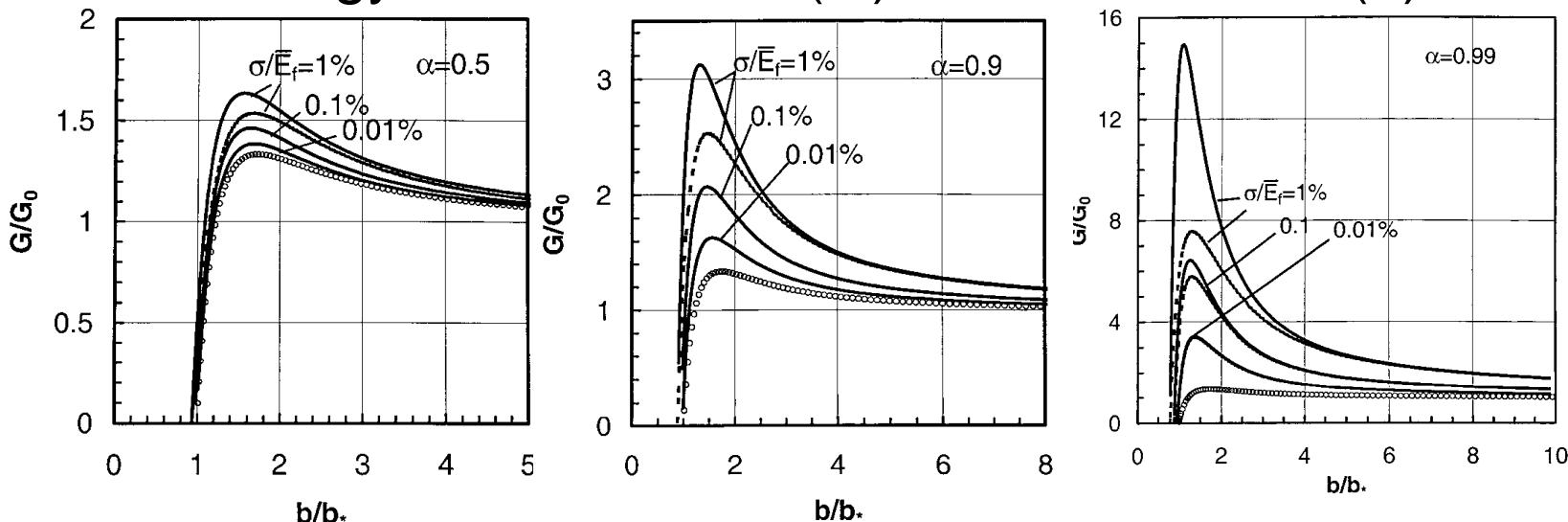


Extra Slides



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Energy Release Rate (G) vs Blister Width (b)



Normalization parameters (1 Film, 2 Substrate):

$$G_0 = \frac{1}{2} \frac{\sigma^2 h}{\bar{E}_1}$$

$$b_* = \frac{\pi h}{2\sqrt{3}} \sqrt{\frac{\bar{E}_1}{\sigma}}$$

$$\bar{E}_i = \frac{E_i}{1 - \nu_i^2}$$

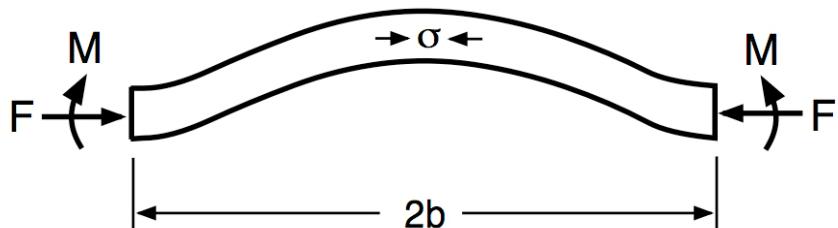
Elastic mismatch characterized by Dundur's parameters:

$$\alpha = \frac{(\bar{E}_1 - \bar{E}_2)}{(\bar{E}_1 + \bar{E}_2)}$$

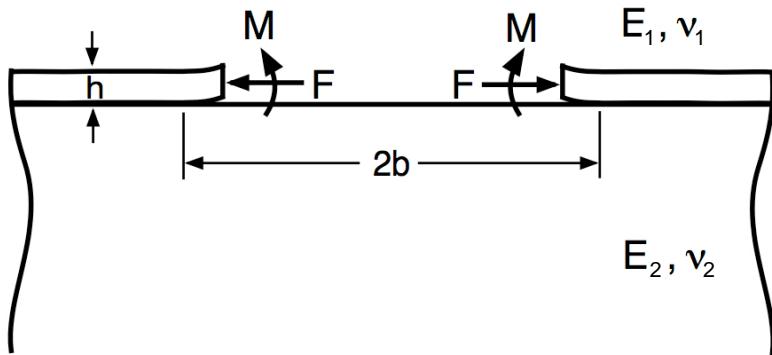
$$\beta = \frac{1}{2} \frac{\mu_1(1 - 2\nu_2) - \mu_2(1 - 2\nu_1)}{\mu_1(1 - \nu_2) + \mu_2(1 - \nu_1)} = 0$$



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The buckled portion of the film was modeled using von Karman nonlinear plate theory

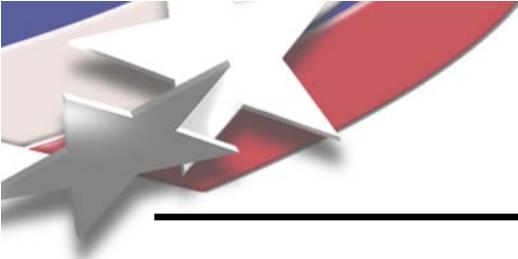


The film/substrate system is a linear plane strain problem solved using an integral equation formulation

The solutions were matched at the detached edges of the film by requiring continuity of displacements and rotations.

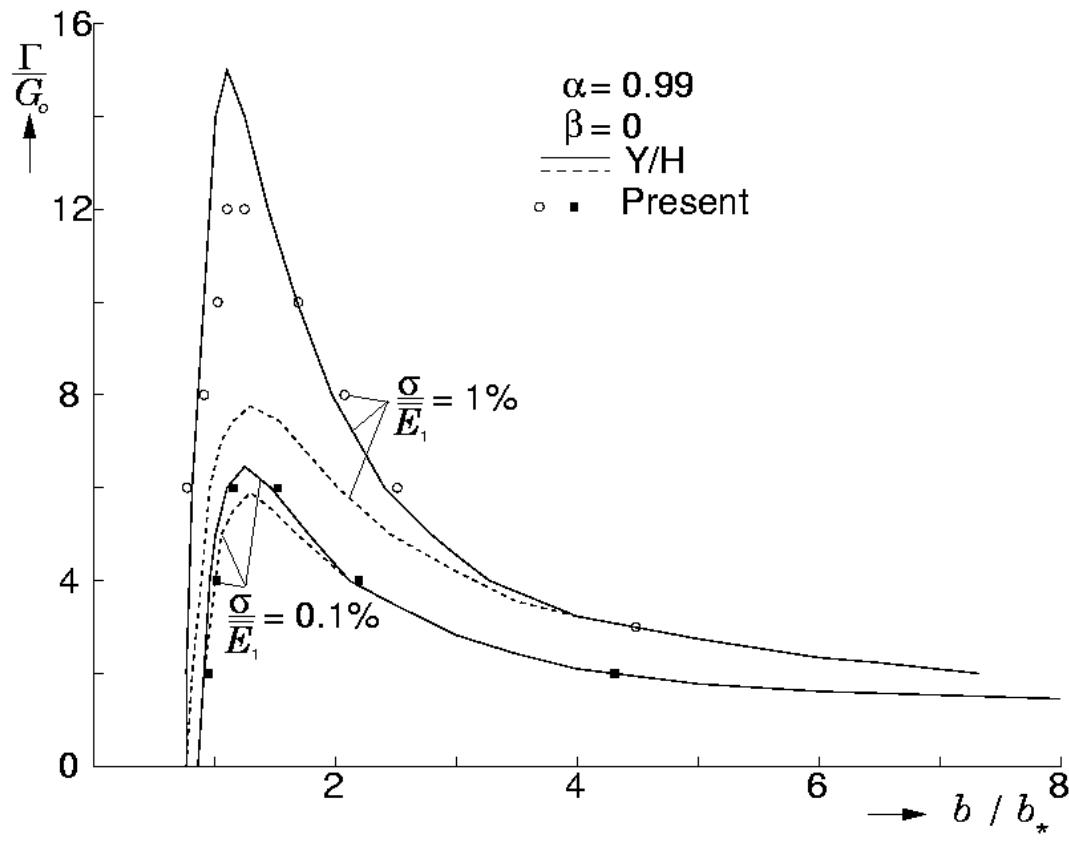


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Yu/Hutchinson Results

$\alpha=0.99$



$$b_* = \frac{\pi h}{2\sqrt{3}} \sqrt{\frac{E_1}{\sigma}}$$



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